

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

PATENT NO. : 6,808,976 B1  
APPLICATION NO. : 09/652714  
DATED : October 26, 2004  
INVENTOR(S) : Vishnu K. Agarwal

Page 1 of 2

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

<u>Column, Line</u>	<u>Reads</u>	<u>Should Read</u>
Column 2, Line 9	"WN <sub>x</sub> /SiO <sub>2</sub> polysilicon"	--WN <sub>x</sub> /SiO <sub>2</sub> /polysilicon
Column 2, Line 15	"Wn <sub>x</sub> ,"	--WN <sub>x</sub> --
Column 3, Line 16	"In yet another"	--Yet another--
Column 6, Line 55	"tantalum pentoxide"	--the tantalum pentoxide--
Column 8, Line 1	"process describe above"	--processed described above--
Column 10, Line 59	Insert claims 27 & 28 as follows:	--27. The method in claim 22 further comprising depositing a plug on which the first conductive layer is thereafter deposited, and wherein exposing the second conductive layer to a thermal process comprises flowing the second conductive layer.

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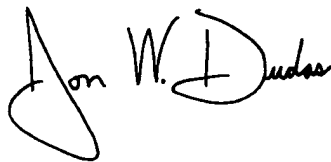
Page 2 of 2

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28. The method in claim 22,  
wherein exposing the  
conductive layer to a thermal  
process comprises exposing  
the conductive layer to an  
alloy process.--

Signed and Sealed this

Eighth Day of January, 2008

A handwritten signature in black ink, appearing to read "Jon W. Dudas". The signature is stylized with a large, looped initial "J" and a distinct "D" at the end.

JON W. DUDAS  
*Director of the United States Patent and Trademark Office*